

IN THE ABSTRACT:

Please cancel the current abstract and insert the following. A marked-up copy showing the changes made to the abstract is attached hereto in Appendix A.

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-- An exposure apparatus for illuminating a pattern with light from a light source and for exposing a predetermined surface with light from the pattern includes (i) a projection optical system for projecting the pattern onto the predetermined surface, the projection optical system having at least one optical element having optical surfaces, and (ii) a gas supplying device for locally supplying a gas to the at least one optical element. In one aspect, the gas supplying device directly blows the gas toward one of the optical surfaces of the at least one optical element, which is closest to the predetermined surface, from the predetermined surface side. --

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IN THE SPECIFICATION:

Please amend the specification as follows:

Please substitute the paragraph beginning at page 1, line 15, with the following. A marked-up copy of this paragraph, showing the changes made thereto, is attached in Appendix A.

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-- Semiconductor integrated circuits have become more and more miniaturized year after year, and, in order to meet this, exposure apparatuses for transferring a circuit pattern onto a wafer are required to have a performance capable of transferring a finer pattern. Thus, the wavelength of exposure light used in such exposure apparatuses becomes shorter and shorter. Currently, i-line (wavelength 365 nm) or KrF excimer laser light (wavelength 245 nm) are used